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IAP12 Rec'd PCT/PTO 25 AUG 2006

PATENT
8017-1194

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Katsumi MAEDA et al. Conf.

Application No. NEW NATIONAL PHASE Group

Filed August 25, 2006 Examiner

STYRENE DERIVATIVE, STYRENE POLYMER, PHOTOSENSITIVE RESIN COMPOSITION, AND METHOD FOR FORMING PATTERN

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

August 25, 2006

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

Amendments to the Claims are reflected in the listing of claims which begin on page 2 of this paper.

Remarks begin on page 6 of this paper.